

# PROLITH by KLA-Tencor

## Photolithography Modeling Software

Training is available through [CULearn...](#) sign up for course:

RSRCH - CNF - PROLITH Video Training

- [NetID Link](#)
- [GuestID Link](#)

In-person assistance may be give one-on-one to interested users by request. Group sessions may also be scheduled on request.

KLA-Tencor's software licensing sponsorship requires that PROLITH by KLA-Tencor be **ONLY available to academic users** of CNF.

## Description:

Projection Lithography simulation software for prediction of printed patterns in photoresist. Includes interactions of light sources, optics, photoresist and film stack, as well as processing parameters.

## Academic Research Use Only:

**PROLITH is available for academic research use only.** Users with both industrial and academic research projects must only use this software for the academic research projects.

User may not use the Software for any activity which is a work for hire or performed under contract to conduct proprietary research or create proprietary work product for government agencies or private, commercial enterprises

## Acknowledgement Requirements:

If User publishes any papers, abstracts, or similar publications, User will acknowledge PROLITH and/or/KLA products in use by USER, in any an all such papers, abstracts, or similar publications that may result from the use of the (Prolith) Software. User shall also identify "PROLITH by KLA" as a sponsor on its group web pages.

KLA requests that user cite the ["PROLITH by KLA" product page](#).

## Capabilities:

EUV, 193nm, 248nm, i-line, and g-line sources, conventional and shaped illumination, polarization, binary and phase shift masks, OPC, immersion, double-patterning, wafer topology, etch results, GDS-II import/export, result file/graphic export.

## Processes Available:

Swing curve, Bosung curve, 2D resist profile, 3D resist profile, dose to clear, dose to print, OPC, flare, Zernike aberrations.

## Applications:

Prediction of swing curve, process parameters, resist profile, pattern shape, mask design, stepper optimization.

## Documentation:

[PROLITH by KLA-Tencor Product Page](#)

[PROLITH by KLA-Tencor Training Document](#)